

10771553\_CLS  
Most Frequently Occurring Classifications of Patents Returned  
From A Search of 10771553 on May 27, 2004

Original Classifications

17	250/288
5	204/452
5	210/198.2
3	204/453
3	216/2
3	250/281
2	204/451
2	204/603
2	210/656
2	216/79

Cross-Reference Classifications

20	250/288
14	250/281
14	250/282
10	210/748
9	210/243
8	204/603
7	204/600
7	204/601
7	210/198.2
7	210/656
5	250/423R
5	438/743
4	204/452
4	204/604
4	438/723
3	216/67
3	216/79
3	250/292
3	436/161
3	438/734
3	438/736
3	438/942
2	204/450
2	204/451
2	216/39
2	216/47
2	216/80
2	422/70
2	436/173
2	436/174
2	436/177

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2 436/86  
2 436/87  
2 436/89  
2 436/91  
2 436/93  
2 436/94  
2 438/756

Combined Classifications

37 250/288  
17 250/281  
14 250/282  
12 210/198.2  
10 204/603  
10 210/748  
9 204/452  
9 210/243  
9 210/656  
8 204/601  
7 204/600  
5 216/79  
5 250/423R  
5 438/743  
4 204/451  
4 204/453  
4 204/604  
4 438/723  
3 216/2  
3 216/67  
3 250/292  
3 436/161  
3 436/173  
3 438/734  
3 438/736  
3 438/942  
2 204/450  
2 216/39  
2 216/47  
2 216/80  
2 250/289  
2 422/70  
2 436/174  
2 436/177  
2 436/86  
2 436/87  
2 436/89  
2 436/91  
2 436/93

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2 436/94  
2 438/756

# 10771553\_CLSTITLES

Titles of Most Frequently Occurring Classifications of Patents Returned

From A Search of 10771553 on May 27, 2004

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37 250/288      (17 OR, 20 XR)
    Class 250 : RADIANT ENERGY
    250/281      IONIC SEPARATION OR ANALYSIS
    250/288      .With sample supply means

17 250/281      (3 OR, 14 XR)
    Class 250 : RADIANT ENERGY
    250/281      IONIC SEPARATION OR ANALYSIS

14 250/282      (0 OR, 14 XR)
    Class 250 : RADIANT ENERGY
    250/281      IONIC SEPARATION OR ANALYSIS
    250/282      .Methods

12 210/198.2    (5 OR, 7 XR)
    Class 210 : LIQUID PURIFICATION OR SEPARATION
    210/198.1    WITH MEANS TO ADD TREATING MATERIAL
    210/198.2    .Chromatography

10 204/603      (2 OR, 8 XR)
    Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY
    204/193      APPARATUS
    204/600      .Electrophoretic or electro-osmotic apparatus

    204/601      ..Capillary electrophoresis type
    204/603      ...With detailed detection system (e.g.,
                  including a light source and a camera, etc.
)

10 210/748      (0 OR, 10 XR)
    Class 210 : LIQUID PURIFICATION OR SEPARATION
    210/600      PROCESSES
    210/748      .Utilizing electrical or wave energy (directly
                  applied to liquid or material being treated
)

9 204/452      (5 OR, 4 XR)
    Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY
    204/450      .Electrophoresis or electro-osmosis processes
                  and electrolyte compositions therefor where
n not provided for
                  elsewhere
    204/451      ..Capillary electrophoresis

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204/452           ...With detailed detection

9. 210/243           (0 OR, 9 XR)  
     Class    210 : LIQUID PURIFICATION OR SEPARATION  
     210/243       ELECTRICAL INSULATING OR ELECTRICITY  
                   DISCHARGING

9 210/656           (2 OR, 7 XR)  
     Class    210 : LIQUID PURIFICATION OR SEPARATION  
     210/600       PROCESSES  
     210/656       .Chromatography

8 204/601           (1 OR, 7 XR)  
     Class    204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY  
     204/193       APPARATUS  
     204/600       .Electrophoretic or electro-osmotic apparatus  
     204/601       ..Capillary electrophoresis type

7 204/600           (0 OR, 7 XR)  
     Class    204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY  
     204/193       APPARATUS  
     204/600       .Electrophoretic or electro-osmotic apparatus

5 216/79            (2 OR, 3 XR)  
     Class    216 : ETCHING A SUBSTRATE: PROCESSES  
     216/58        GAS PHASE ETCHING OF SUBSTRATE  
     216/74        .Etching inorganic substrate  
     216/79        ..Etching silicon containing substrate

5 250/423R           (0 OR, 5 XR)  
     Class    250 : RADIANT ENERGY  
     250/423R       ION GENERATION

5 438/743           (0 OR, 5 XR)  
     Class    438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS  
     438/689        CHEMICAL ETCHING  
     438/706        .Vapor phase etching (i.e., dry etching)  
     438/735        ..Differential etching of semiconductor  
                   substrate  
     438/737        ...Substrate possessing multiple layers  
     438/743        ....Silicon oxide or glass

4 204/451           (2 OR, 2 XR)  
     Class    204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY  
     204/450        .Electrophoresis or electro-osmosis processes

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not provided for  
 204/451 ..Capillary electrophoresis  
 elsewhere

4 204/453 (3 OR, 1 XR)

Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY

204/450 .Electrophoresis or electro-osmosis processes  
 and electrolyte compositions therefor whe

n not provided for

204/451 ..Capillary electrophoresis  
 204/453 ...With injection  
 elsewhere

4 204/604 (0 OR, 4 XR)

Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY

204/193 APPARATUS

204/600 .Electrophoretic or electro-osmotic apparatus

204/601 ..Capillary electrophoresis type

204/604 ...With injector

4 438/723 (0 OR, 4 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/689 CHEMICAL ETCHING

438/706 .Vapor phase etching (i.e., dry etching)

438/707 ..Utilizing electromagnetic or wave energy

438/710 ...By creating electric field (e.g., plasma,  
 glow discharge, etc.)

438/723 ....Silicon oxide or glass

3 216/2 (3 OR, 0 XR)

Class 216 : ETCHING A SUBSTRATE: PROCESSES

216/2 ETCHING OF SEMICONDUCTOR MATERIAL TO PRODUCE A

N

ARTICLE HAVING A NONELECTRICAL FUNCTION

3 216/67 (0 OR, 3 XR)

Class 216 : ETCHING A SUBSTRATE: PROCESSES

216/58 GAS PHASE ETCHING OF SUBSTRATE

216/63 .Application of energy to the gaseous etchant  
 or to the substrate being etched

216/67 ..Using plasma

3 250/292 (0 OR, 3 XR)

Class 250 : RADIANT ENERGY

250/281 IONIC SEPARATION OR ANALYSIS

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250/290 .Cyclically varying ion selecting field means

250/292 ..Laterally resonant ion path

3 436/161 (0 OR, 3 XR)  
 Class 436 : CHEMISTRY: ANALYTICAL AND IMMUNOLOGICAL  
 TESTING  
 436/161 INCLUDING CHROMATOGRAPHY

3 436/173 (1 OR, 2 XR)  
 Class 436 : CHEMISTRY: ANALYTICAL AND IMMUNOLOGICAL  
 TESTING  
 436/173 NUCLEAR MAGNETIC RESONANCE, ELECTRON SPIN  
 RESONANCE OR OTHER SPIN EFFECTS OR MASS SPE  
 CTROMETRY

3 438/734 (0 OR, 3 XR)  
 Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS  
 438/689 CHEMICAL ETCHING  
 438/706 .Vapor phase etching (i.e., dry etching)  
 438/734 ..Sequential etching steps on a single layer

3 438/736 (0 OR, 3 XR)  
 Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS  
 438/689 CHEMICAL ETCHING  
 438/706 .Vapor phase etching (i.e., dry etching)  
 438/735 ..Differential etching of semiconductor  
 substrate  
 438/736 ...Utilizing multilayered mask

3 438/942 (0 OR, 3 XR)  
 Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS  
 438/942 MASKING

2 204/450 (0 OR, 2 XR)  
 Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY  
 204/450 .Electrophoresis or electro-osmosis processes  
 and electrolyte compositions therefor when  
 not provided for elsewhere

2 216/39 (0 OR, 2 XR)  
 Class 216 : ETCHING A SUBSTRATE: PROCESSES  
 216/39 FORMING GROOVE OR HOLE IN A SUBSTRATE WHICH IS  
 SUBSEQUENTLY FILLED OR COATED

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2 216/47 (0 OR, 2 XR)  
 Class 216 : ETCHING A SUBSTRATE: PROCESSES  
 216/41 MASKING OF A SUBSTRATE USING MATERIAL RESISTAN  
 T  
 TO AN ETCHANT (I.E., ETCH RESIST)  
 216/47 .Mask is multilayer resist

2 216/80 (0 OR, 2 XR)  
 Class 216 : ETCHING A SUBSTRATE: PROCESSES  
 216/58 GAS PHASE ETCHING OF SUBSTRATE  
 216/74 .Etching inorganic substrate  
 216/79 ..Etching silicon containing substrate  
 216/80 ...Silicon containing substrate is glass

2 250/289 (1 OR, 1 XR)  
 Class 250 : RADIANT ENERGY  
 250/281 IONIC SEPARATION OR ANALYSIS  
 250/289 .With evacuation or sealing means

2 422/70 (0 OR, 2 XR)  
 Class 422 : CHEMICAL APPARATUS AND PROCESS DISINFECTING,  
 DEODORIZING, PRESERVING, OR STERILIZING  
 422/50 ANALYZER, STRUCTURED INDICATOR, OR MANIPULATIV  
 E  
 LABORATORY DEVICE  
 422/68.1 .Means for analyzing liquid or solid sample  
 422/69 ..Sorption testing  
 422/70 ...Liquid chromatography

2 436/174 (0 OR, 2 XR)  
 Class 436 : CHEMISTRY: ANALYTICAL AND IMMUNOLOGICAL  
 TESTING  
 436/174 INCLUDING SAMPLE PREPARATION

2 436/177 (0 OR, 2 XR)  
 Class 436 : CHEMISTRY: ANALYTICAL AND IMMUNOLOGICAL  
 TESTING  
 436/174 INCLUDING SAMPLE PREPARATION  
 436/177 .Liberation or purification of sample or  
 separation of material from a sample (e.g.,  
 filtering,  
 centrifuging, etc.)

2 436/86 (0 OR, 2 XR)  
 Class 436 : CHEMISTRY: ANALYTICAL AND IMMUNOLOGICAL  
 TESTING  
 436/86 PEPTIDE, PROTEIN OR AMINO ACID



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2	436/87	(0 OR, 2 XR)
	Class	436 : CHEMISTRY: ANALYTICAL AND IMMUNOLOGICAL TESTING
	436/86	PEPTIDE, PROTEIN OR AMINO ACID
	436/87	.Glycoproteins (e.g., hormone, etc.)
2	436/89	(0 OR, 2 XR)
	Class	436 : CHEMISTRY: ANALYTICAL AND IMMUNOLOGICAL TESTING
	436/86	PEPTIDE, PROTEIN OR AMINO ACID
	436/89	.Amino acid or sequencing procedure
2	436/91	(0 OR, 2 XR)
	Class	436 : CHEMISTRY: ANALYTICAL AND IMMUNOLOGICAL TESTING
	436/91	HETEROCYCLIC CARBON COMPOUND (I.E., O, S, N, Se, Te, AS ONLY RING HETERO ATOM)
2	436/93	(0 OR, 2 XR)
	Class	436 : CHEMISTRY: ANALYTICAL AND IMMUNOLOGICAL TESTING
	436/91	HETEROCYCLIC CARBON COMPOUND (I.E., O, S, N, Se, Te, AS ONLY RING HETERO ATOM)
	436/93	.Hetero-O (e.g., ascorbic acid, etc.)
2	436/94	(0 OR, 2 XR)
	Class	436 : CHEMISTRY: ANALYTICAL AND IMMUNOLOGICAL TESTING
	436/91	HETEROCYCLIC CARBON COMPOUND (I.E., O, S, N, Se, Te, AS ONLY RING HETERO ATOM)
	436/93	.Hetero-O (e.g., ascorbic acid, etc.)
	436/94	..Saccharide (e.g., DNA, etc.)
2	438/756	(0 OR, 2 XR)
	Class	438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
	438/689	CHEMICAL ETCHING
	438/745	.Liquid phase etching
	438/756	..Silicon oxide